

# ASML Twinscan XT 1250 D ArF Scanner, 12"

Asset ID: 36999



#### Configuration and Photos on Following Pages

To our knowledge, the information contained in this data sheet is accurate, but it may contain errors and we do not warrant the completeness or accuracy of this data.

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QUICK LEAD TIMES



QUALITY









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QUICK LEAD TIME



QUALITY EQUIPMENT





#### Configuration:

- 193nm
- Track Pre-warning signal (APR)s: APR enabled
- Avoid Track INPUT/OUTPUT conflicts, Raise AS after APRs: Avoid Track
- INPUT/OUTPUT conflicts enabled
- Active wafer release for dry WSs: FALSE
- Closing disk types: No closing disk present
- Safeguard to prevent loading of reticles with too wide or mispositioned pellicles: Disabled Continuous clampable wafer table for dry WSs: Absent
- Type of wafer table on chuck 1 & 2 for immersion machines: Zerodur version 1
- WS Immersion throughput packages: None
- WS Immersion thermal control packages: None
- Wafer Stage Configurations: Wafer Stage type 2 configuration
- Wafer Carrier Locations: Right
- Wafers per Carriers: 25
- Wafer Mark Sensors: Absent
- Wafer Id Readers: Absent
- Wafer Tracks: Present
- Wafer Stage Types: Dual Chuck
- Wafer Stress Relaxations: FALSE
- Lower Docking Plates: Present
- WS Balance Masss: Stainless Steel
- WH Robot Power Amplifiers: CPM 20
- Wafer Stage Fast Stiff X Move Electronics: Present
- Wafer Stage Mirror Block Down Electronics: Present
- Universal Prealignments: Disabled
- Interferometer axis version at exposures: 3 plus 1 axis
- Wafer Handling Pneumaticss: Dedicated
- Wafer Switchs: Absent











- Chuck 1 & 2 wafer sizes: 300mm
- Type of immersion hood for immersions: None
- Specifies chuck1 & 2 layout relev. for Immersions: Chuck does not support immersion
- Specifies chuck1 & 2 configs: Dry
- Specifies chuck1 & 2 versions: not specified
- Changed Short Stroke diff XY controllers: Disabled
- Docking wheels at WH unloads: Present
- Docking plate heights: Low
- Immersion Hood versions: Absent
- Carrier Handler Types: Mark I 300 Foup
- Wafer Handling Load & Unload Robot Types: Double Fold Arm, 12 mm Z stroke
- Wafer Handling Store Units: Absent
- Wafer Handler wrt BF Shifted in Zs: Not Shifted
- Reticle streaming lites: Disabled
- Enhancements in Reticle Monitors: no enhancements
- Reticle streaming: Disabled
- Improvements for reticle handlings: Disabled
- Extend IRIS maximum particles scanned to 50000.s: Absent
- Zeroing type for Encoders Measurement Systems: Using extra hall sensors for zeroing
- Reticle Stage Chuck Types: Glued Leafspring, TYPE\_2: Glued LS, Pneum. GC, IFM / ENC Nitrogen purging of Reticle Stages: RS is not purged
- Reticle Carrier Locations: Right
- Integrated Reticle Inspection Systems: PPD1 with IRIS1 functionality
- Integrated Reticle Librarys: IRL with original functionality











- Reticle Sizes: 6 inch
- Reticle Carrier Tag Readers: Present
- Reticle Stage Long Stroke Motor Types: Cobalt Ferro 18 teeth
- Reticle Stage Long Stroke Configs: TYPE\_3: CoFe\_18 motor, SB controlled, int. vacuum supply, pneum GC
- Automated Reticle Transport Systems: Absent
- Reticle Stage Lenscooler Boxes: Lenscooler Box with anti-aliasing Filter
- Maximum Reticle ID Lengths: 24 Characters
- Reticle Stage Measurement System on Scans: Heidenhain Encoders
- Relative direction of ws to rs on the X axis: Same
- RS Object Fields: Normal
- Reticle exchange types: Retex option: E
- Iris feature Scans: Absent (Overrules Absent)
- Reticle Handler types: Original
- 2D Barcode Readers: Absent
- Integrated Reticle Inspection System Configurations: Disable creation of OSIRIS viewable files.
- WS Immersion Hood Only Testrigs: Absent
- Version of RS/WS IO librarys: Version 1
- Dynamic Performance Calculations: Mark 1
- Stages Sample Rates: 5.0 kHz
- Interferometer Electronics: Ifsr
- Capacitive z-height sensor type.s: Dual Z sensor board
- Ifm config at measure sides: 8 axes
- Dose System Performance Test sequences: Test sequence 1
- PEP-ADC Intensitys: Disable PEP-ADC Intensity
- Online Lamp Peak: Disable Online Lamp Peak

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- Dose Intensity Optimizations: Dose Intensity Optimization
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- Wafer Handling Load & Unload Robot Types: Double Fold Arm, 12 mm Z stroke
- Wafer Handling Store Units: Absent
- Wafer Handler wrt BF Shifted in Zs: Not Shifted
- Reticle streaming lites: Disabled
- Enhancements in Reticle Monitors: no enhancements
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- Online Lamp Peak: Disable Online Lamp Peak
- Dose Intensity Optimizations: Dose
- Intensity Optimization
- Test Table Z Axiss: Worm Wheel
- PUPICOMs/ Architectures: Present/ DC Motor with gearbox Number of Z Lens Manipulatorss: 5
- Number of Active Lens Elementss: 1
- Number of Bi-directional Active Lens Elementss: 0
- Number of Active Manipulator Elementss: 0
- Number of Active Elementss: 1
- Number of Half Dome Mirrorss: 0
- Number of Semi-Active X-Y Lens Manipulatorss: 4

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QUALITY EQUIPMEN





- Setup sensor board versions: Setup SSD version 1
- Imaging Generic Power Amplifiers: Generic Power Amplifier Imaging Control Rack Configurations: IPDR
- Type of projection multiplexer boards: MUX Absent
- LFC Rack in Electronic Architectures: Present
- Projection GPA Configuration Versions: Version 2
- Number of Lens NEXZ Manipulatorss: 5
- Number of Lens Z Manipulators Using Camdisks: 0 Spotsensor surface coatings: Bilatal
- Energy Sensors: VLOC
- Spot Sensor Chuck 1s & 2s: VLOC
- Modelling for MAXYSs: Absent
- Uniformity Improvement Packages: Present
- Number of pre-amps available per Z-manipulators: 0 Immersions: Absent
- Pupil measurements with ILIASs: Present
- Automatic CUAs: Absent
- Beam Controls: Beam adjustment
- Extended Spot Sensor Matchings: Present Number of Rxms/ Ryms: 5/5
- Diaphragm Limiters: Absent
- NA1 motor types: None
- Spot Sensor Reticle Stages: Absent
- Smooth Field Uniformitys: Absent
- Exchangeable Last Lens Elements: Present
- Exchangeable Pupil Lens Elements: Absent
- Number of manipulable ELLE axess: 0
- UV Shutter versions: UV Shutter version 1
- Dosecontrol Hardwares: ISBIlluminator platforms: Aerial 2











- Polarizations: Absent
- Automatic PCE exchangers: Absent
- Automatic CUA exchanger architectures: Not applicable Test table architectures: Aerial 2
- Illumination modes: All illumination modes
- DUV Lightsource Power Levels: 45.00 Watt
- Lens Top Tool Connections: Lens Top Tool can be mounted on top of the Lens Scanning Energy Sensor Calibrations: Static Energy Sensor Calibration
- Position of Spot Sensor on Chuck 1s: Spot Sensor Position on Chuck 1 layout 1
- Position of Spot Sensor on Chuck 2s: Spot Sensor Position on Chuck 2 layout 1
- Z-capture for low relfectivity wafers: Off
- TIS plate deformation corrections: Disabled
- FSM Flexibility packages: Disabled
- Field width optimised leveling: Disabled
- Constrained fits: Disabled
- Levelling throughput improvement on measure sides: No levelling throughput package
- Point-to-Point LS Machine Matchings: Disabled
- Circuit Dependent FECs: Present
- Focus Monitorings: Present
- Extended LS areas: Disabled
- Air Gauges: Absent
- Type of Air Gauges: No Air Gauge device present
- Reticle shape corrections: Disabled (Overrules Enabled)
- LS focus nodes: LS focus node 3
- Level Sensor Processing Racks: LCSR
- LS\_PEMM\_CONFIGs: Present









- LS\_CPU\_CONFIGs: 3 CPU's available

- Base Liner overlay high order intrafields: Disabled

- BaseLiner focus high order intrafields: Disabled

- BaseLiner focus control.s: Disabled

- Pattern Matcher fullchips: Absent

- Pattern Matchers: Absent

- Maximum numerical aperature (NA) that can be used in Lot Productions: level 0

- Log missed translations: Disabled

- Allow even orders usages: Present

- Multilingual UIs: Absent

- Improved Maintenance action scheduling.s: Disabled

- Recipe Creators: Light

- Lot Report Data Categorys: Enhanced Diagnostics

- CDCs: Enabled

- EFESEs: Absent

PED control modes: AbsentProximity Matchings: Present

mbds controls: Present

- Enhanced exposures 1s: Present

- Data collection not covered by FOCUS and - OVERLAYs: InformPro Data Collection disabled

- Overlay Data Collections: Disabled

- XML Lot Report Content Levels: Basic

- Enable the Maintenance Assistants: Disable Maintenance Assistant

- EDA Interfaces: Disabled

- Equipment Constants via SECS interfaces: Disabled











- LCI WaitWatcher plug-ins: Absent

- Reorder Lot Services: Absent

- Shot Data Collections: Absent

- Focus Data Collections: Absent

- Alignment Recipe Overrides: Disabled

- Enable to support SMASH XY mark types.s: not supported

- Specifies which mark types are supporteds: ASML marks only

- Alignment laser configurations: 2 color laser

- OADB Improved Dynamic Ranges: Disabled

- Board configurations: ODB + ADB

- Alignment Camera Mirrors: Absent

- Athena Narrow Marks Twinscans: Present

- Alignment Sensor Types: Athena Narrow Marks OM

- Athena Focus Improvements 1s: Present

- Max alignment speeds: Setting 2

- AA processing racks: AACR processing rack

- Particle Extraction Mass Flow Meters: Absent

purging configurations: purging CONFIG 3

- Bubble Extraction Seal Settings: Not Applicable

- Ultra Pure Water flow controller (WICC)s: absent

- LCW Circuit set-ups: Flow Version 1

- In situ Wafer TablesStone Cleanings: Absent

- Clean Air Configurations: Others

- Metroframe Circuit Water Cabinets: Absent - CT Miscellaneous Racks: Present

- Clean Air Temperature Controls: Driver and ACC

- Purge Hoods configurations: Compressed Clean air and Extremely Clean Dry air Nitrogen Purge Utility Controls: Absent









- Reticle Cleanings: AbsentMetroframe types: TYPE\_I
- Inlet restriction for clean airs: Inlet restriction at right side
- Reticle Stage purged mini environments: Present
- Gas Control Unit Types: High Flow (HF)
- Wet Imaging Control Cabinets: Not Applicable
- Readout location of Pneumatic Facility Unit sensors: Machine Base Diagnostics System (MBDS)
- Laminar Bottom Hoods: Absent
- Extreme Clean Humiditied Airs: Absent
- Lens Circuit Water Flows: High
- Motor Circuit Water Flows: Normal
- SPM temp correction for lens axiss: Disabled
- 2 Sided IFM-beams for WS-X (expose/ measure)s: Not available
- Diff pressure correction for IFM beams: Absent
- IFM Laser Configurations: AOM Recombo Laser
- Position Control Rack Configurations: Rack Configuration type 3
- Position Control Power Rack Configurations: TYPE\_3: Stages Power Rack upto E-spec Number of Motion Controllerss: 5 Motion Controllers present
- Position Control Motion Control racks: PMCR
- Reticle Stage Short Stroke X/Y11/Y12/Y21/Y22/Y11/Y11 amp.s: PADC 100V/16A
- Wafer Stage Short Stroke 1 XY1/ XY2/XY3 amp.s: PADC 100V/16A
- Wafer Stage Short Stroke 2 XY1/ XY2/XY3 amp.s: PADC 100V/16A
- Reticle Stage Short Stroke Z1/Z2/Z3 amp.s: Pass Low Current 8.5A
- Wafer Stage Short Stroke 1 Z1/Z2/Z3 amp.s: Pass Low Current 8.5A
- Wafer Stage Short Stroke 2 Z1/Z2/Z3 amp.s: Pass Low Current 8.5A











- Reticle Stage Long Stroke Y11/Y12/Y21/Y22 amp.s: 450V20A: PAAC AT-pepD
- Reticle Balance Mass 1/2 amp.s: 450V20A: PAAC AT-pepD
- Wafer Stage Long Stroke E/M X amp.s: 400V16A: PAAC AT-D
- Wafer Stage Long Stroke E Y1/Y2/CS amp.s: 400V16A: PAAC AT-D
- Wafer Stage Long Stroke M Y1/Y2/CS amp.s: 400V16A: PAAC AT-D
- Wafer Stage Balance Mass 11/12/21/22 amp.s: 325V14A: PAAC AT-C
- Pressure update rate for fringelength corrections: Pressure update rate 2 or 4 Hz
- TestStreams: TestStream disabled
- Performance Enhancement Packages: None
- PEP Image Streamings: Present
- Lot Overhead Reductions: LOR2
- Extended Zone Alignments: Disabled
- Intrafield Higher Order Process Correctionss: Disabled
- SMASH Reuse Capture Information in Stage Alignments: Coarse capture scans are done on all stage alignment marks.
- Allow wafer plane deviation check with Focus Monitorings: Disabled
- Parameter indicates how long overlay data will be stored.s: Short retention period.
- Level sensor Ry drift corrections: Disabled
- Fading Control Switchs: Disabled
- Improved wafer reject modes: Disabled
- Automated Lens Heating Calibrations: Disabled
- Lens heating History in LH Feedforwards: Enabled
- Allow different Exp, TIS Align sets: Absent
- Imaging Fading Controls: Disabled
- Gridmappers: Disabled
- 2D grid corrections: Enabled

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- Double TIS scans: Disabled
- Symmetrical Reticle Alignments: Disabled Ast offset correction in TIS LHFB/LOCO (Version 3)s: Enabled
- Choice of avoidance routing.s: Absent
- NEXZ-tilt per exposures: The NEXZ-tilt cannot be adjusted per exposure.
- Off-axis slits: Projection lens has no off-axis slit.
- Improved Edge Field Levelings: Disabled
- Enhanced Throughput Reticle Alignments: Present
- Wavelength Adjustables: Adjustable
- Allow L1L7 Type 1 Optimizations: Absent
- Lot Alignment Report Encryptions: Unencrypted
- Stage Alignment Filters: Present
- Lot Correction Sequences: Unencrypted
- Stage Alignment Filters: Present
- Lot Correction Sequences: Type B
- Lens Heating Feedbacks: Present
- Application Specific Lens Heating Calibration and Verifications: Present Improved
- Contrast Controls: Absent
- ILIAS lens setups: Absent
- Air Gauge Improved Levellings: Absent
- Process Dependent Gain Corrections: Absent
- Enhanced Exposure Overlays: Absent
- ALE 1 Uses: Lens heating only
- Overlay Nodes: Level 0
- E-chuck Flatness Qualification Tests: Disabled
- TOP HDs: Absent











- Reticle Align High Precisions: Absent
- LS spot coverages: Absent
- Layout Version Number TIS Plate 1 on Chuck 1s/2s: TIS Plate 1 Layout Version 2
- Layout Version Number TIS Plate 2 on Chuck 1s2s: TIS Plate 2 Layout Version 4
- Usage of wavelength/ Energy Sensor data by TISs: Disabled
- Indication what kind of AM controller hardware is presents: SUCR
- Piezo Active Lens Mountss: Absent
- ILIAS Functionality For Lithoguides: Present
- ISIS Functionality For Lithoguides: Absent
- SAMOS Stray Light Test For Lithoguides: Present
- PUPIL Measurement For Lithoguides: Present
- FOCAL Measurement for Lithoguides: Present
- Leveling Verification Test for Lithoguides: Present
- Lithoguide Imaging Recipess: Absent
- Dose System Performance Test for Lithoguides: Present
- ILIAS Sensor Locations: Chuck 2
- ILIAS sensor type chuck 2s: Multiple scan grid
- ILIAS sensor type chuck 1s: None
- Reticle Level Polarization Sensors: Absent SASO robustness and fiber connectivitys: Disable SASO robustness
- Extended X width masking ranges: Disabled
- PDO offset for EFL LS spots: Disabled
- Assure System Snapshotss: not allowed
- Insert a delay time before starting a Lot (lens heating).s: Enabled
- Save throughput data to the disks: Disabled Patch strategys: Patchlevel
- Chuck Dedications: Basic











- Application Types: Scanner Application

- Number of RMCS clients: No clients

- MDL Viewers: Site View

- ZERO Fiducials: ILIAS MK2

- Machine Architectures: XT Machine Architecture

- XT Architecture Revisions: Rev1

- Machine Types: 1250

- Machine Specifications: pep-D Specification - Stand-alone Workstations: FALSE

- CP 1As/1Bs/2s/3s/4s/5s/6s: Absent- Wafer Handler Productivitys: Level 0







